

A new phase of aluminium silicon carbide, Al₄Si₂C₅

X-ray powder diffraction data of α - and β -aluminium silicon carbide of Al₄SiC₄ was reported by Barczak [1] in 1961. Subsequently, a new unit cell dimension of α -phase different from Barczak's was proposed by Schneider [2] in 1978. He gave a new index, different from that given by Barczak on the X-ray powder diffraction profiles of the α -phase.

We have recently succeeded in synthesizing a new compound of aluminium silicon carbide, Al₄Si₂C₅. An attempt has been made to determine the unit cell dimensions of this new compound. The X-ray powder diffraction pattern has been successfully indexed here.

Silicon carbide (a product of Ibigawa Denko Co Ltd, β -type, particle size < 3 μ m, the purity > 99.9%, oxygen content \approx 0.2 wt %) and Al₄C₃ powder (a product of Alfa Products Co, - 100 mesh) were mixed according to the composition of Al₄Si₂C₅ with a ball mill made of polyethylene. Approximately 3 g of the mixture was packed into a graphite die (15 mm diameter) and heated at a rate of 50° Cmin⁻¹ to 1970° C in an argon atmosphere. The specimens were maintained at that temperature for a few minutes and then rapidly cooled by turning off the electric power of the heater. The time constant calculated from the recorded cooling curve was \sim 3 min. During this procedure, hot-pressing of the specimen was avoided in order to prevent the extrusion of the specimen from the die. After cooling, the recovered specimen was crushed and powdered for the X-ray investigation. The X-ray powder diffraction data showed that the specimen consisted mainly of Al₄Si₂C₅ together with a small amount of α -phase.

The X-ray powder diffraction data was taken by Rigaku Geigerflex using CuK α X-ray radiation with an Ni-filter and a scintillation counter detector scanning at 2 θ - 1° per minute. The reflections were collected in the 2 θ -range from 10° to 110°. The X-ray diffraction symmetry in the single crystal method [3] revealed that the space group of the crystal belongs to R $\bar{3}m$ or R3*m*. The unit cell dimension is $a_0 = 13.50 \text{ \AA}$, $\alpha = 13.83^\circ$ in the rhombohedral lattice and $a = 3.25 \text{ \AA}$, $c = 40.11 \text{ \AA}$ in the hexagonal lattice.

Using the hexagonal cell dimension mentioned above, the powder diffraction profiles were

successfully indexed in the range of 2 θ from 10° to 110°. The calculated and observed planar spacings, observed 2 θ , and observed intensity distribution I/I_0 are shown in Table I together with their indexes.

The new compound, Al₄Si₂C₅ was synthesized only when the ingredients were rapidly quenched

TABLE I X-ray powder diffraction data for Al₄Si₂C₅. In this table, hkl refer to the hexagonal unit cell

hkl	d_{calc}	d_{obs}	2 θ_{obs}	I/I_0
003	13.37	13.37	6.60	12
009	4.46	4.46	19.91	10
*00·12	3.34	3.35	26.57	90
101	2.81	2.81	31.86	71
10 $\bar{2}$	2.79	2.79	32.07	59
00·15	2.67	2.67	33.48	27
10 $\bar{5}$	2.66	2.66	33.71	31
107	2.53	2.53	35.49	5
10 $\bar{8}$	2.46	2.45	36.59	41
10·10	2.30	2.30	39.05	62
10· $\bar{11}$ } 00·18 } 10·13 } 10·16 } 10· $\bar{17}$ } 110 } 10·22 } 10· $\bar{23}$ } 20 $\bar{1}$ } 202 } 11·15 } 205 } 208 } 10· $\bar{26}$ } 20· $\bar{10}$ } 20·11 } 11·18 } 20·13 } 10·28 } 20· $\bar{16}$ } 20·17 } 10· $\bar{32}$ } 20· $\bar{22}$ } 00·36 } 20·23 } 211 } 21 $\bar{2}$ } 10·35 } 21 $\bar{8}$ } 20·26 } 21·10 } 00·39 } 21·16 } 10·40 }	2.23	2.23	40.47	100
	2.08	2.08	43.47	13
	1.87	1.87	48.59	25
	1.81	1.81	50.42	16
	1.63	1.63	56.57	55
	1.53	1.53	60.44	11
	1.48	1.48	62.60	19
	1.41	1.41	66.45	4
	1.40			
	1.39	1.39	67.41	2
	1.36			
	1.35	1.35	69.32	11
	1.33	1.33	70.88	7
	1.31	1.31	71.82	32
	1.28	1.28	74.20	4
	1.23	1.23	77.73	2
	1.21	1.21	79.16	2
	1.15	1.15	84.53	1
	1.11	1.11	87.47	3
	1.10	1.10	89.36	3
	1.06	1.06	92.89	3
	1.04	1.04	95.43	3
	1.03	1.03	96.98	4
	0.98	0.98	103.68	1
	0.95	0.95	109.26	4

* This reflection is affected by the presence of graphite as an impurity.

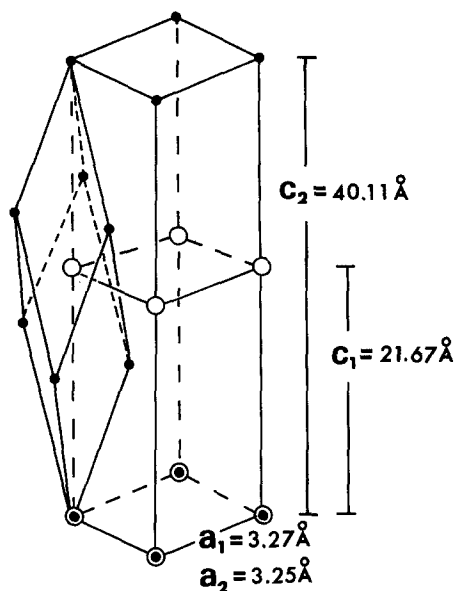


Figure 1 A crystal axial relation between α - Al_4SiC_4 and $\text{Al}_4\text{Si}_2\text{C}_5$ of aluminium silicon carbide. The lattice points of Al_4SiC_4 are shown with white circles and those of $\text{Al}_4\text{Si}_2\text{C}_5$ with black dots. The hexagonal lattice points of the latter corresponding rhombohedral are also given. Suffixes 1 and 2 indicate the lattice of α - Al_4SiC_4 and $\text{Al}_4\text{Si}_2\text{C}_5$, respectively.

from 1970° C to room temperature. If the compound $\text{Al}_4\text{Si}_2\text{C}_5$ is cooled slowly from 1970° C to 1900° C, the $\text{Al}_4\text{Si}_2\text{C}_5$ phase does not appear at all, but α - Al_4SiC_4 phase and silicon carbide are formed. Therefore, this new compound may be considered to be a stable phase at temperatures above 1900° C. Other experimental results showed that at temperatures below 1900° C, α - Al_4SiC_4 is more stable than the $\text{Al}_4\text{Si}_2\text{C}_5$.

The X-ray diffraction profiles of $\text{Al}_4\text{Si}_2\text{C}_5$ are quite different from those of α - and β -aluminium silicon carbide reported by Barczak [1] and

Schneider [2]. The axial relation of the crystal lattices between Al_4SiC_4 and $\text{Al}_4\text{Si}_2\text{C}_5$ is shown in Fig. 1. The a -axis dimension in the hexagonal lattice of $\text{Al}_4\text{Si}_2\text{C}_5$ is very similar to that of α - Al_4SiC_4 and the c -axis dimension of the former is nearly twice as long as the latter.

The intensity distribution of X-ray diffraction and the unit cell dimension of $\text{Al}_4\text{Si}_2\text{C}_5$ are very similar to those of aluminium carbonitride, $\text{Al}_6\text{C}_3\text{N}_2$ reported by Jefferey and Wu [4]. Therefore, the crystal structure of the former may be similar to that of the latter. It can be postulated that the layer structure of $\text{Al}_4\text{Si}_2\text{C}_5$ is formed by substituting the two SiC layers for two AlN layers in the $\text{Al}_6\text{C}_3\text{N}_2$ structure.

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The preparation and properties of single crystal copper phosphide

Copper-phosphorus alloys are used in the metal industry instead of pure phosphorus for deoxidizing brass and bronze alloys and in the preparation of phosphor bronze. As a result there have been several studies of the copper-phosphorus phase

diagram [1-3]. All of the diagrams indicate the presence of a compound with the formula Cu_3P , tricopper phosphide or, more commonly, copper phosphide. The crystal structure and some of the properties have been investigated [4, 5]. This compound has analogues in copper arsenide (Cu_3As) and copper antimonide (Cu_3Sb) and the former has been shown to have semiconducting